

SHORT-WAVE INFRARED PHOTODETECTORS BASED ON COLLOIDAL QUANTUM DOTS

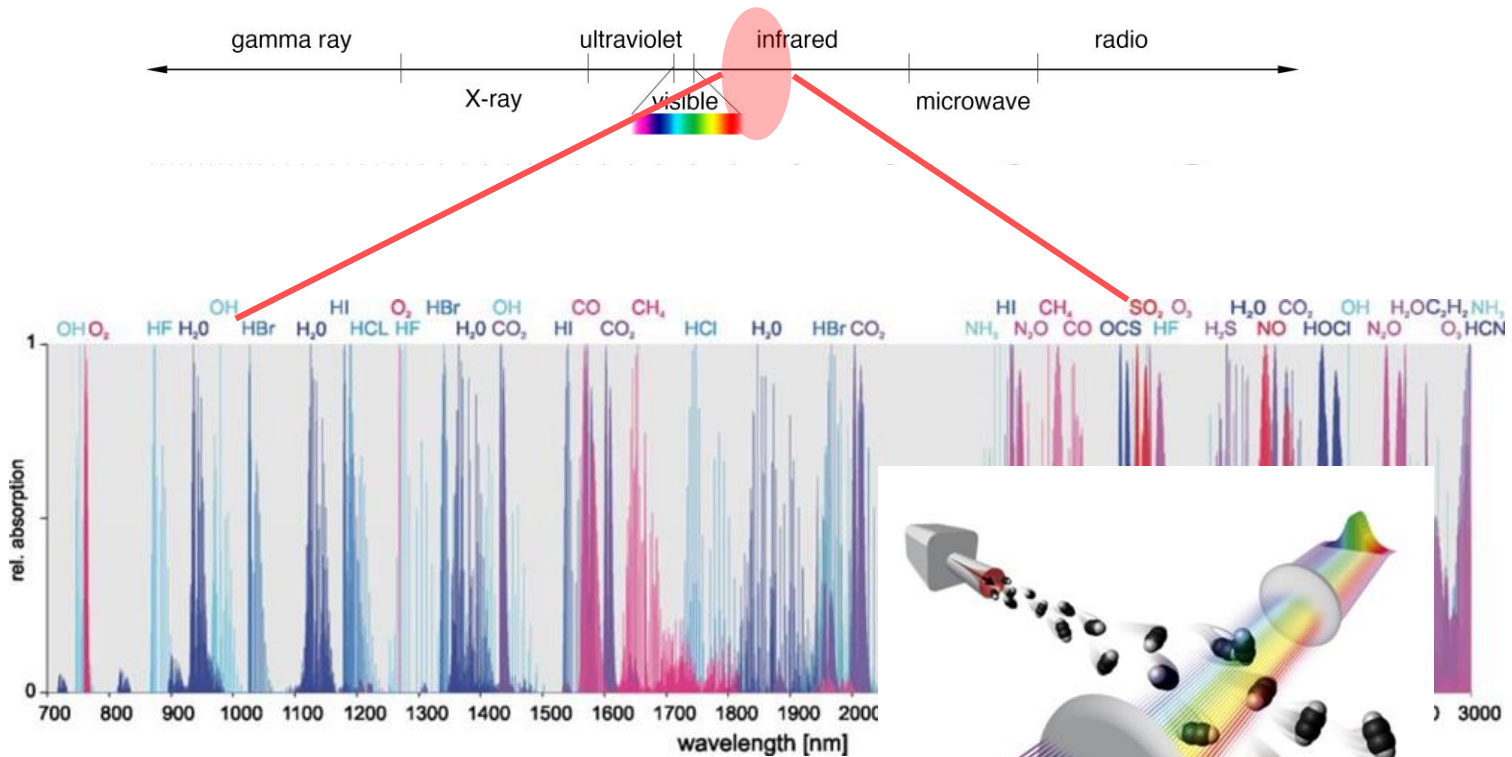
JUNE 13TH 2017

Chen Hu

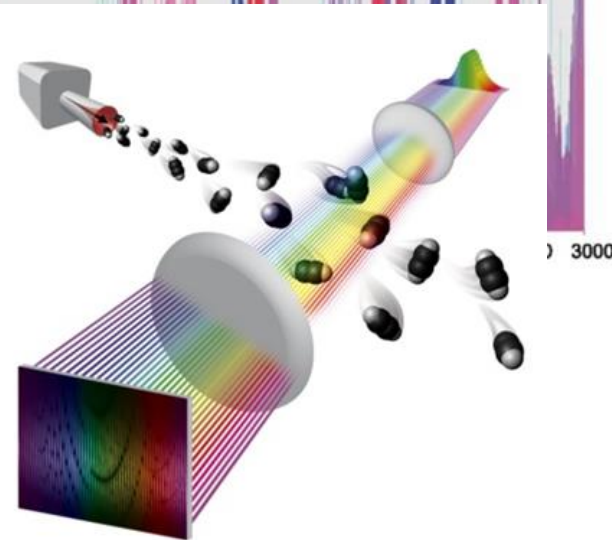
Promoter: Prof. dr. ir. Günther Roelkens
and Prof. dr. ir. Zeger Hens

WHY SHORT-WAVE INFRARED DETECTORS BASED ON QDs?

Short wave infrared: 1-2.5 μm wavelength range



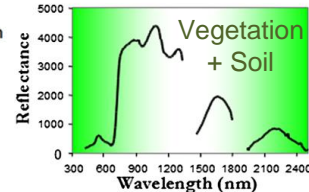
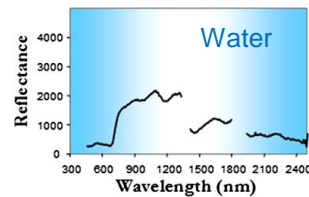
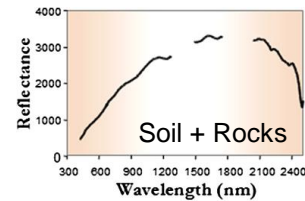
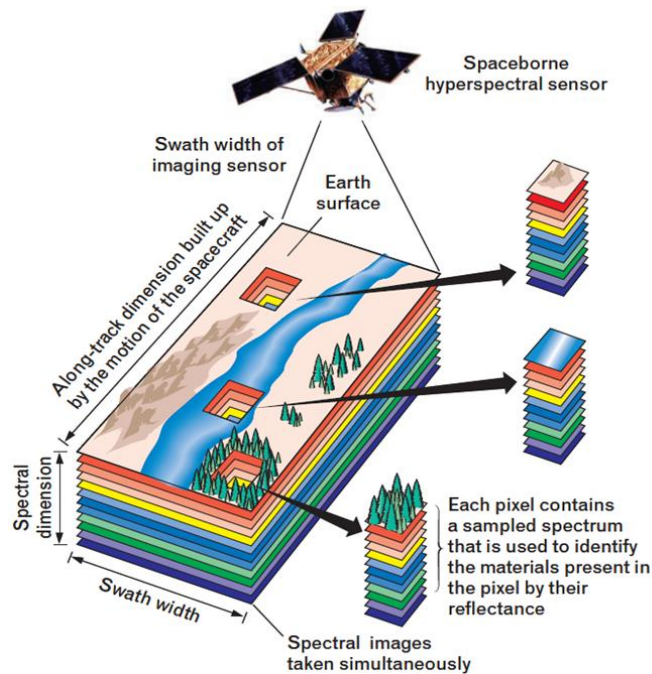
Applications for gas sensing



WHY SHORT-WAVE INFRARED DETECTORS BASED ON QDs?

More Applications:

- Enhanced vision (night vision, through fog)
- Hyperspectral imaging



WHY SHORT-WAVE INFRARED DETECTORS BASED ON QDs?

Current technology:

III-V semiconductors (extended InGaAs based)

epitaxial growth techniques, processes lower yield compared to silicon technology => cost

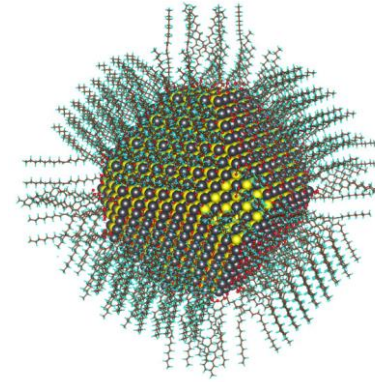
cost limits the number of applications where these camera's / detectors can be applied (e.g. smart phone)



=> Novel approach avoiding epitaxial growth of semiconductors, integration on 200mm/300mm silicon wafers

=> Performance of a SWIR III-V camera at the cost of a visible CMOS camera?

COLLOIDAL QUANTUM DOTS FOR SWIR?



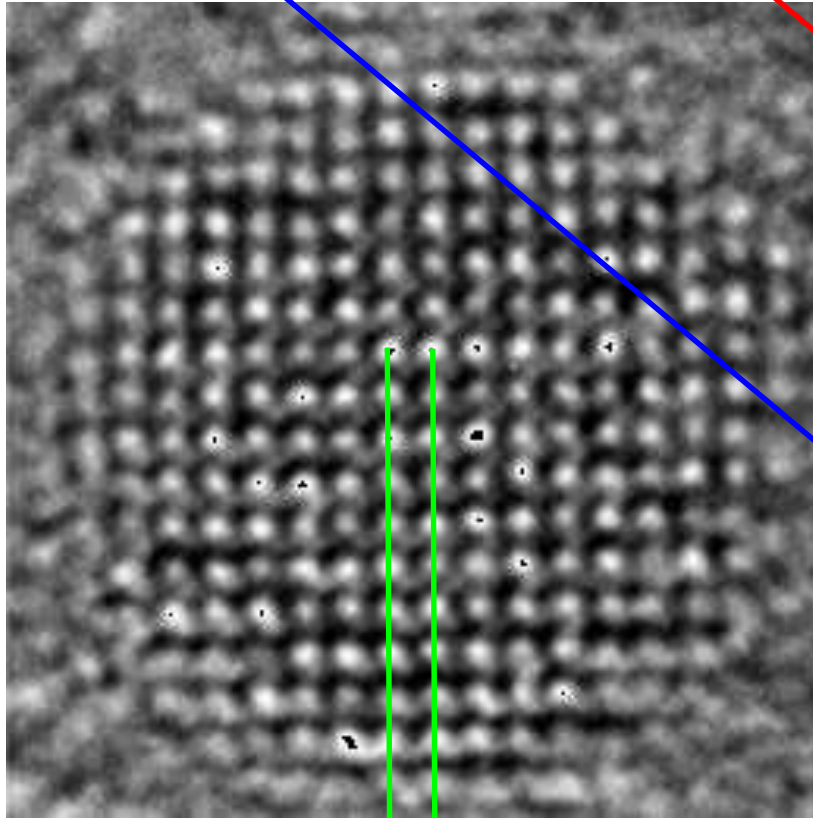
Small box

Confining electrons

(In practice a semiconductor nanocrystal)

**1-1000 nm sized particle
dispersed in a continuous
medium**

(1-20nm for quantum dots)



0.3 nm

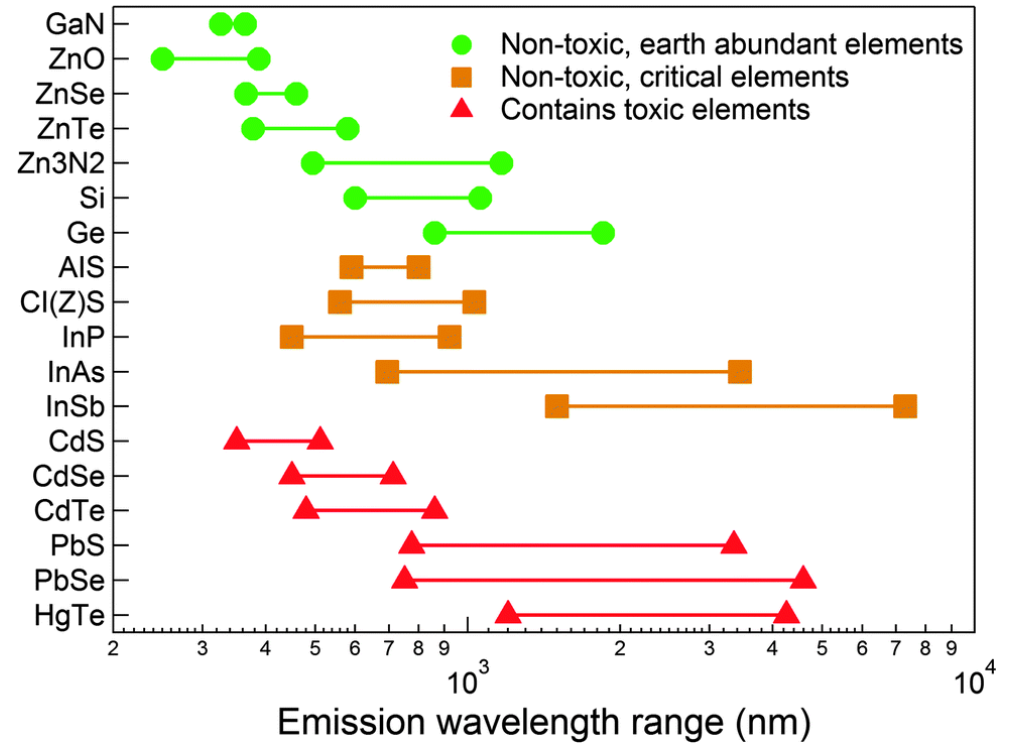
LOW COST THROUGH THE HOT INJECTION SYNTHESIS



Physics and Chemistry of Nanostructures Group

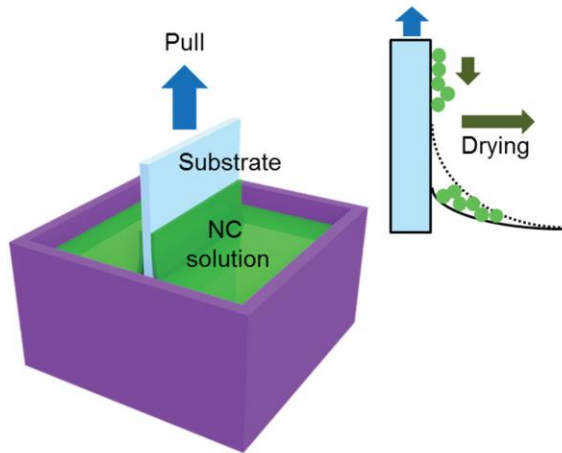
Hot-injection based QD synthesis

SPECTRAL TUNABILITY THROUGH QUANTUM CONFINEMENT EFFECT

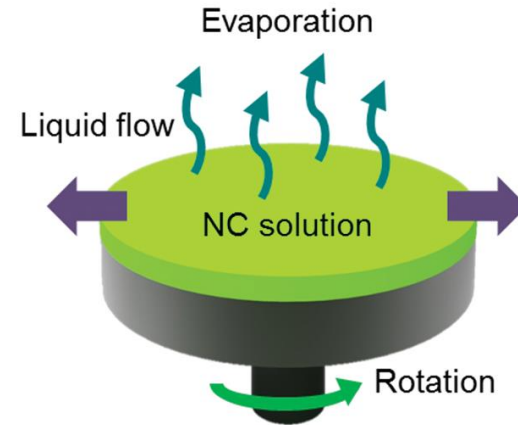


EASY HETEROGENEOUS INTEGRATION ON Si/SOI

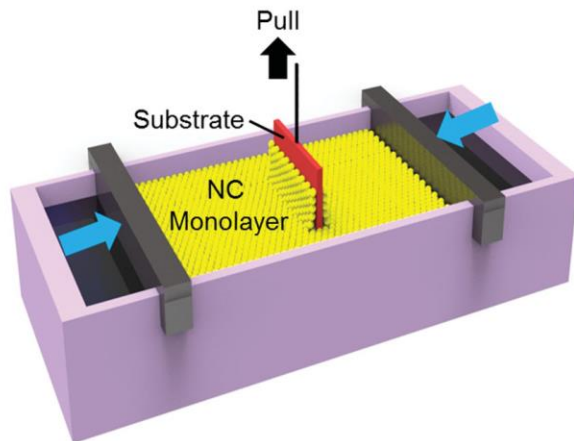
• Dip coating



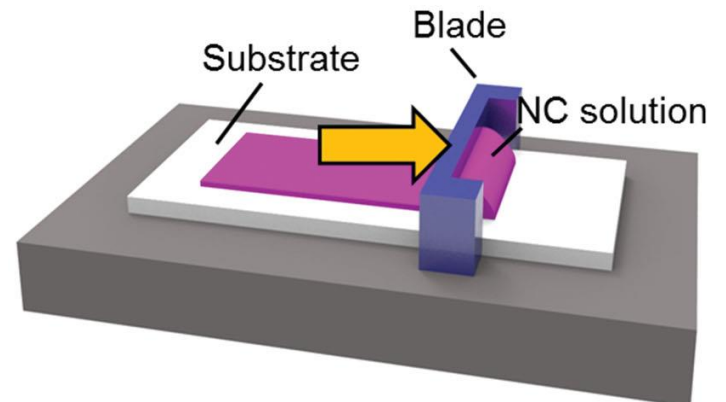
• Spin coating



• Langmuir-Blodgett deposition

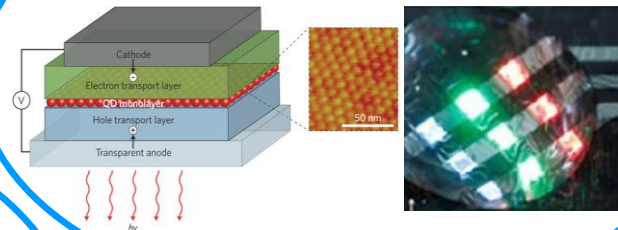


• Doctor blading

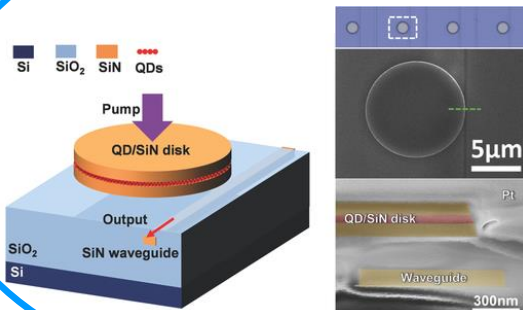


APPLICATIONS BASED ON COLLOIDAL QUANTUM DOTS

Light emitting diodes



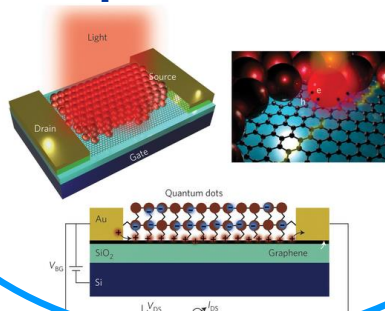
QD based laser



QD display



QD photodetectors



Photovoltaics

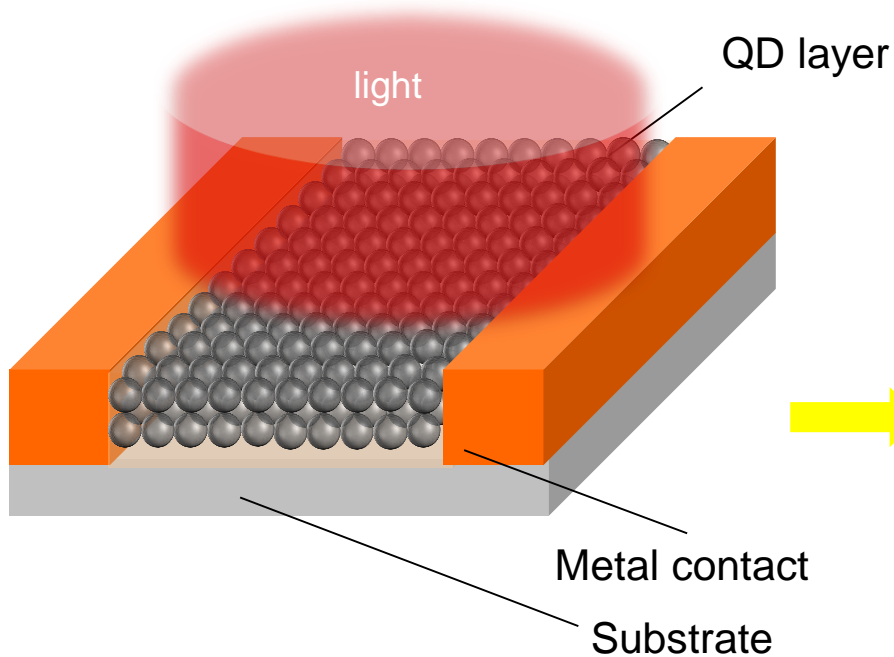


- Introduction
- SWIR/MWIR colloidal quantum dot photodetectors
- Measurement results
- Conclusion and future work

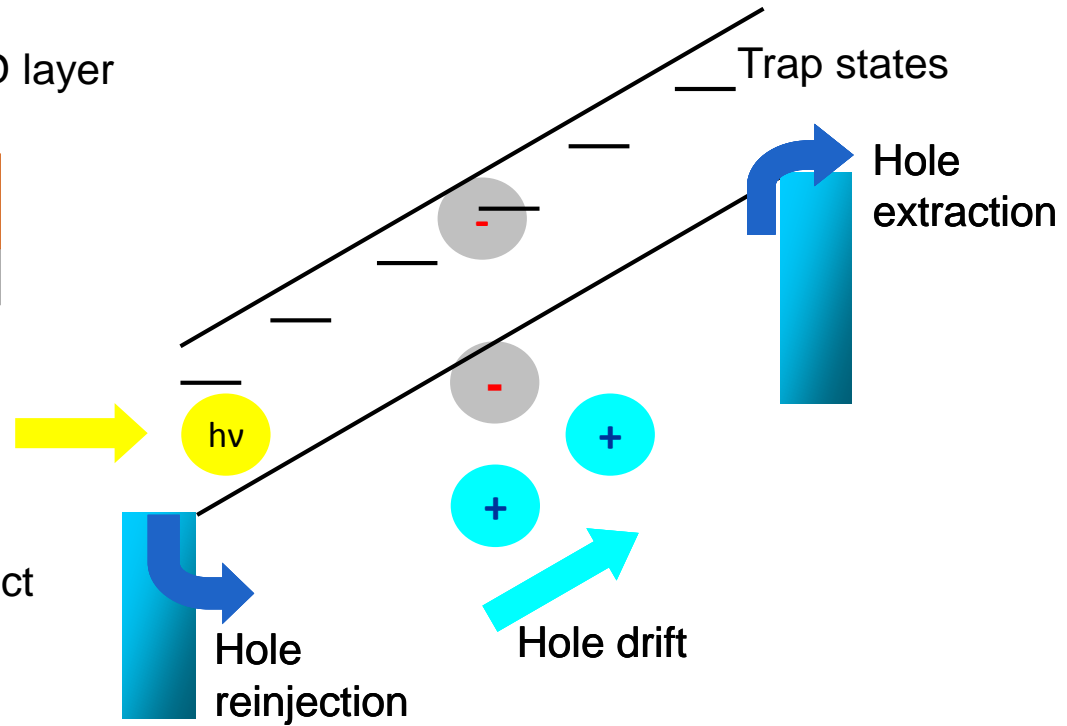
OUTLINE

HOW TO REALIZE PHOTODETECTION?

Integrated MIR QD Photodetectors



Interband transition

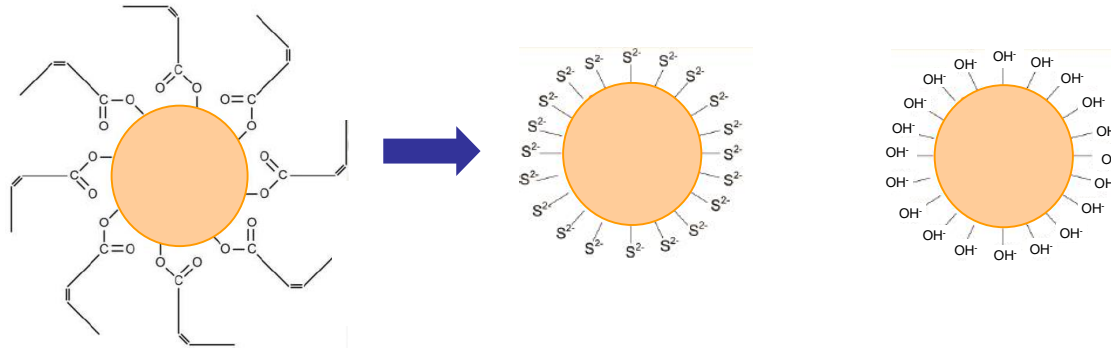


$$\text{Gain} = \text{carrier lifetime} / \text{carrier transit time}$$

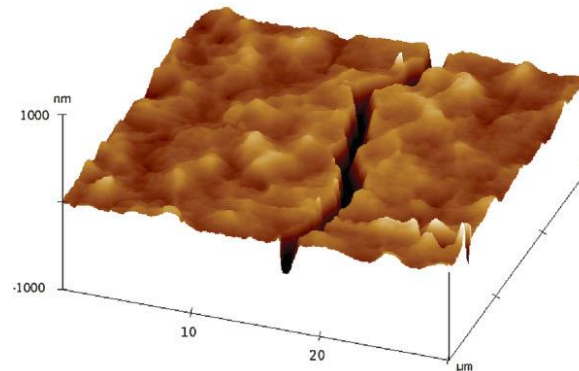
Filling of trap states reduces responsivity at higher input power

CHALLENGES OF INTEGRATION?

- Isolating organics



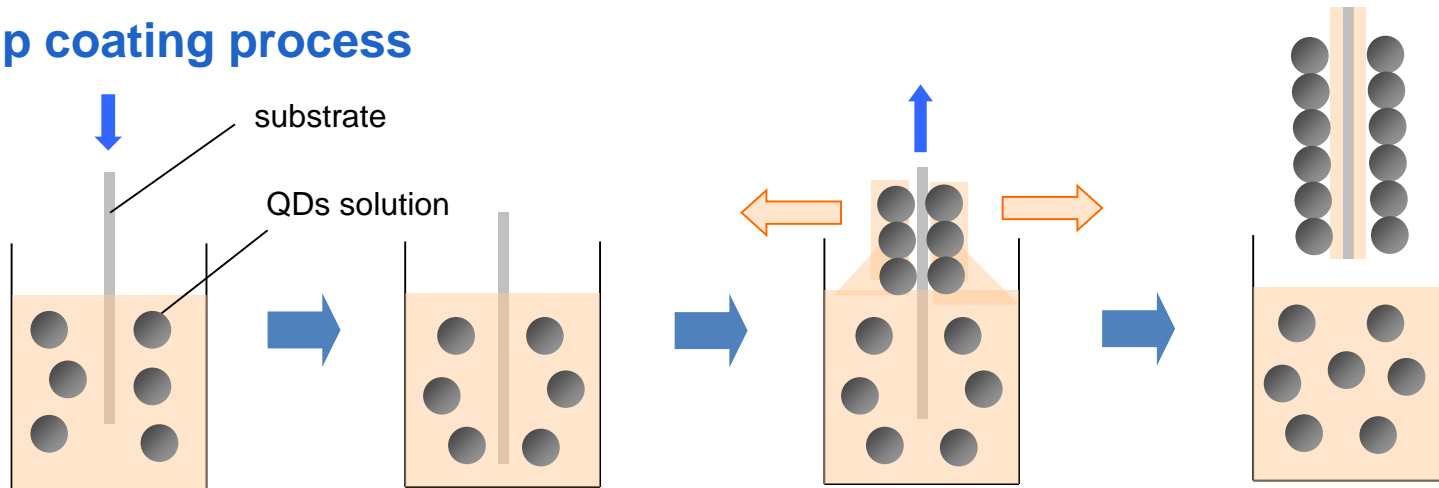
- Film cracking due to significant volume loss during ligand exchange



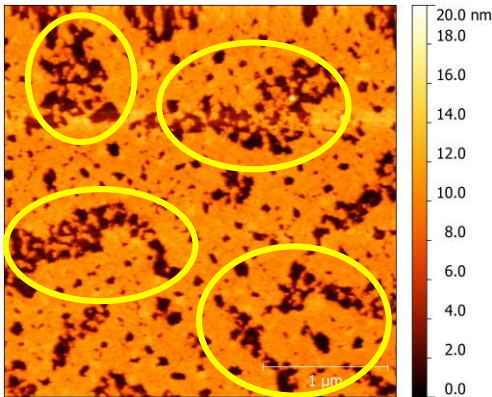
- Patterning of colloidal QD film
- Stability issues (oxidation, etc.)

QUANTUM DOT FILMS FORMED THROUGH DIP COATING

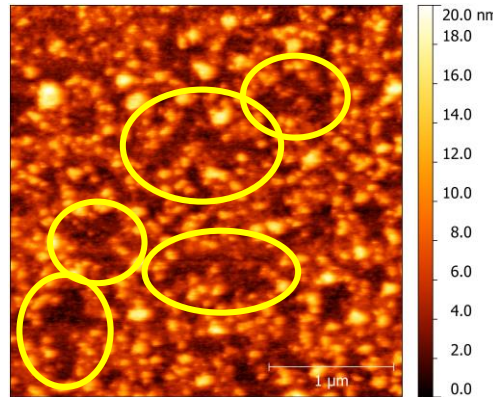
• Dip coating process



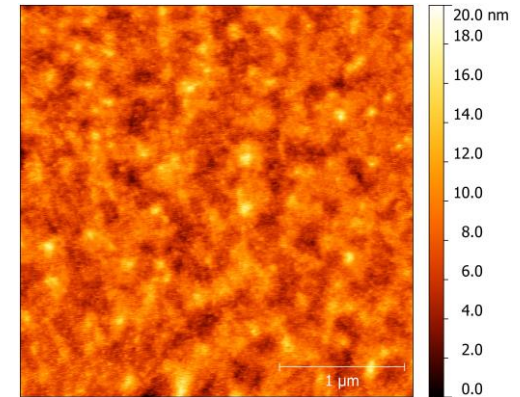
80 mm/min withdrawal speed
and 100 nM concentration



20 mm/min withdrawal speed
and 1 μM concentration



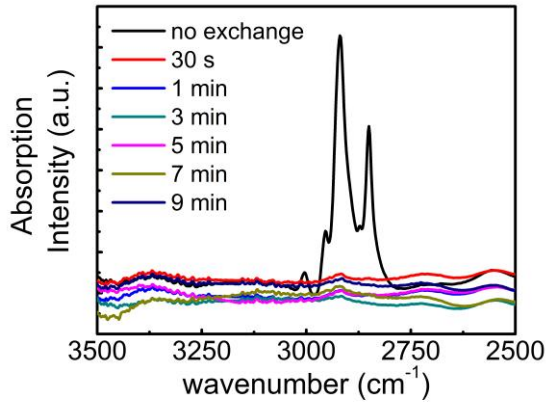
80 mm/min withdrawal speed
and 1 μM concentration



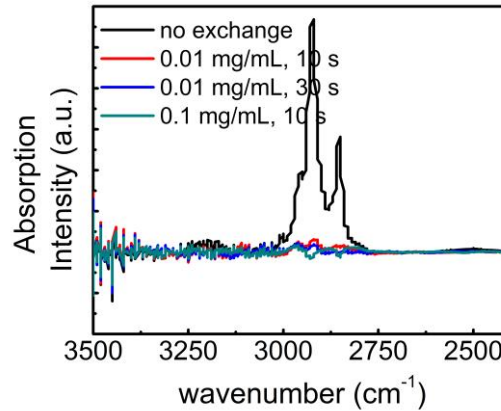
INORGANIC LIGAND EXCHANGE

FTIR measurement:

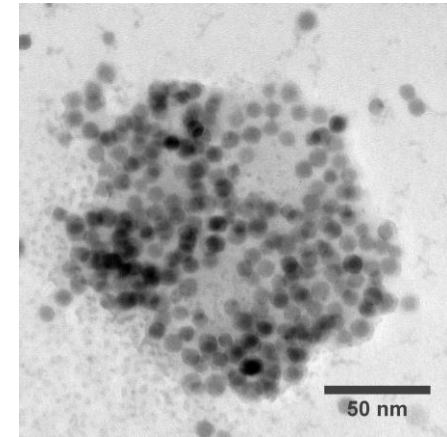
S^{2-} ligand exchange



OH^- ligand exchange

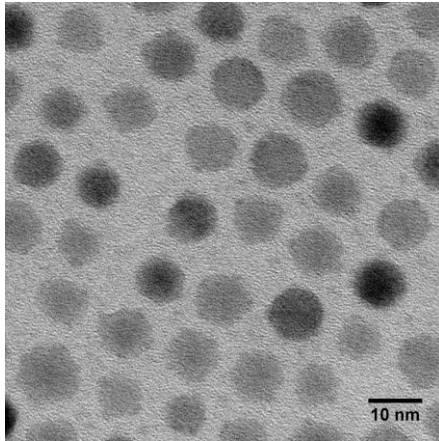


A thorough cleaning is also needed

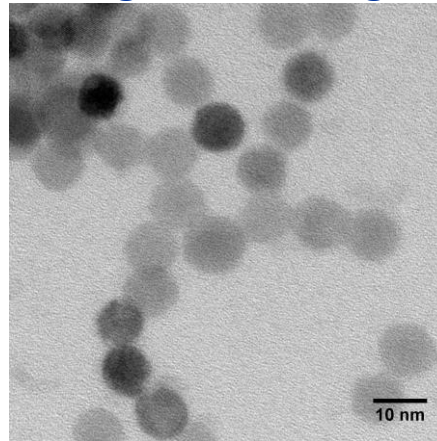


TEM measurement:

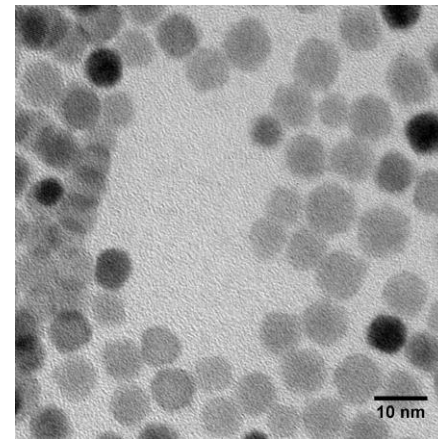
PbS-OIAC QDs



S^{2-} ligand exchange

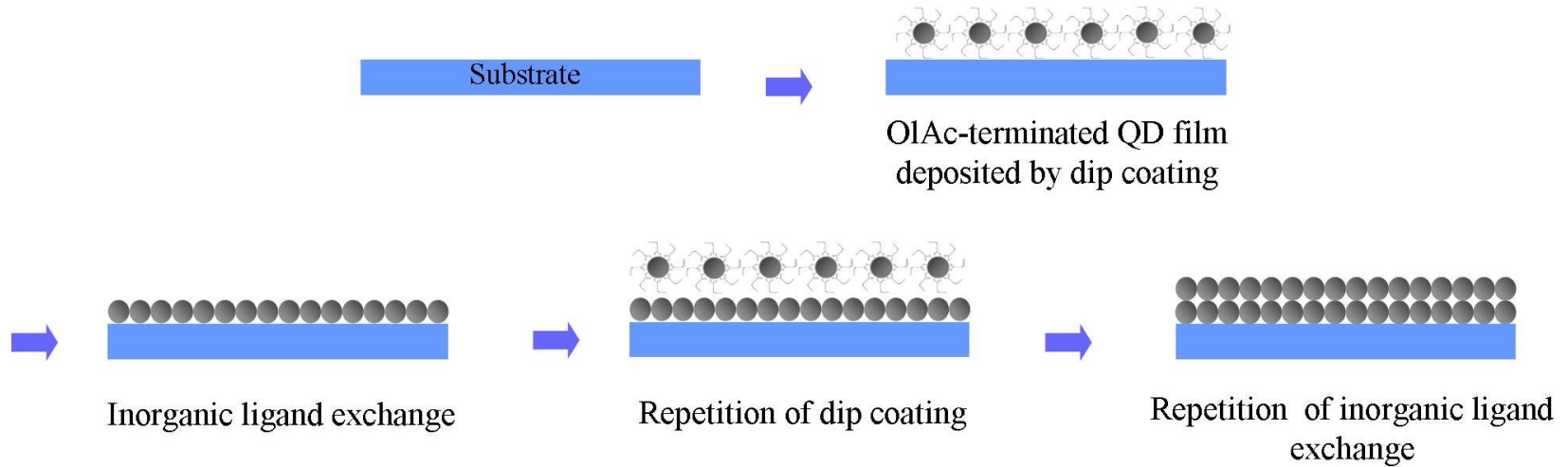


OH^- ligand exchange

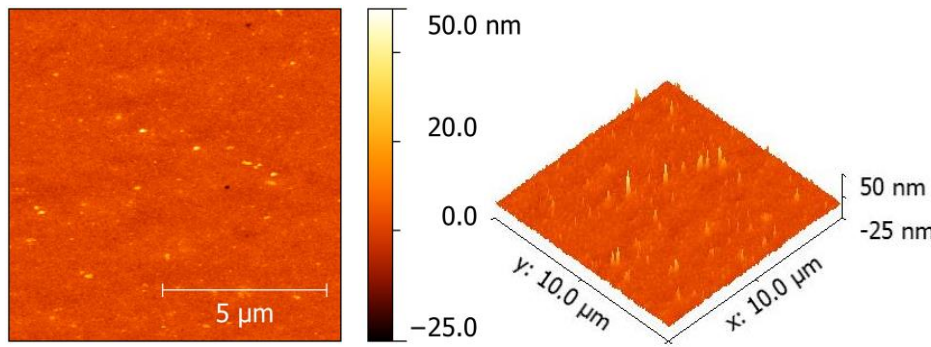


LAYER-BY-LAYER ASSEMBLY METHOD

Process flow:

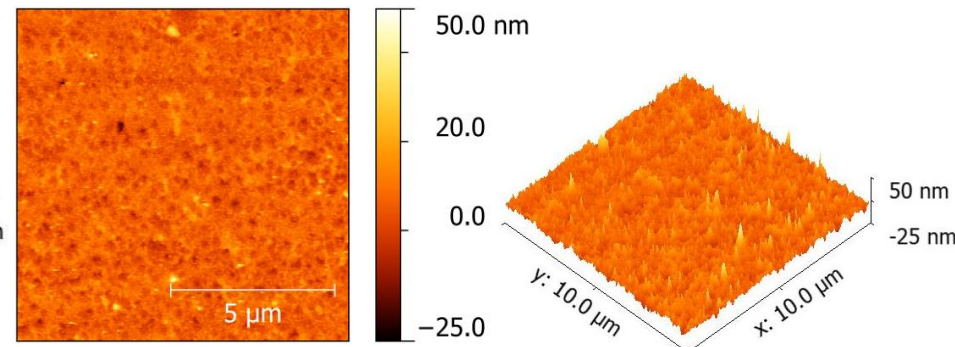


PbS/S²⁻ QD film



RMS Roughness ~ 5.5 nm

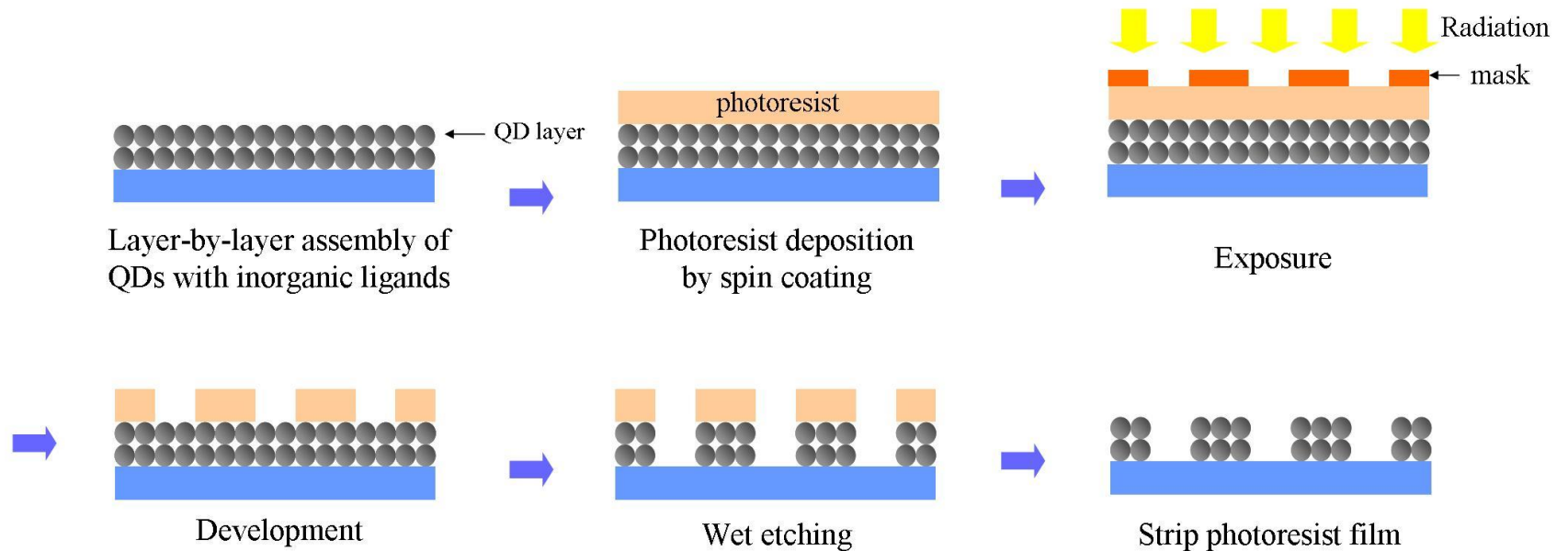
PbS/OH⁻ QD film



RMS Roughness ~ 4.5 nm

PATTERNING OF NANOCRYSTAL FILM BY WET ETCHING

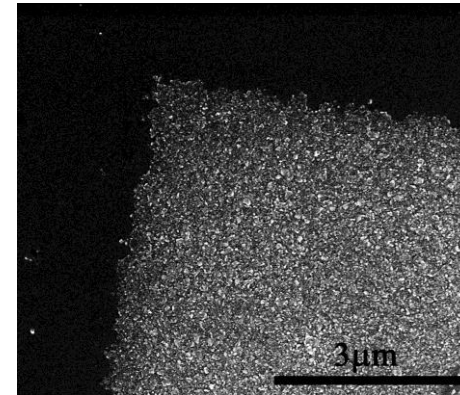
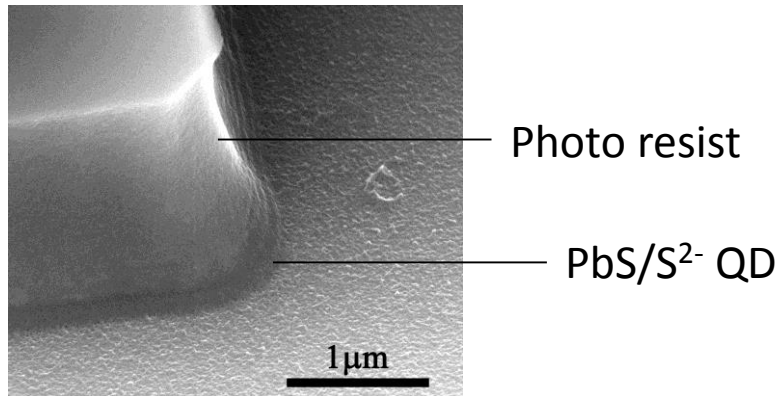
Process flow:



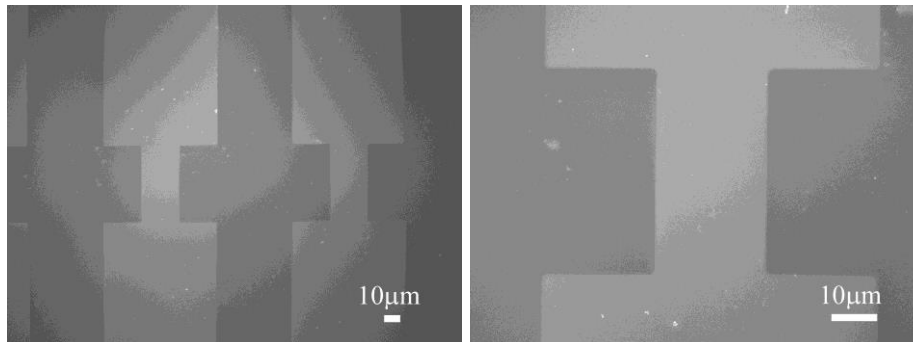
C. Hu, *et al.* "The micropatterning of layers of colloidal quantum dots with inorganic ligands using selective wet etching" *Nanotechnology* **2014**

MICROPATTERNING OF PBS NANOCRYSTAL FILM ON 2D SUBSTRATES

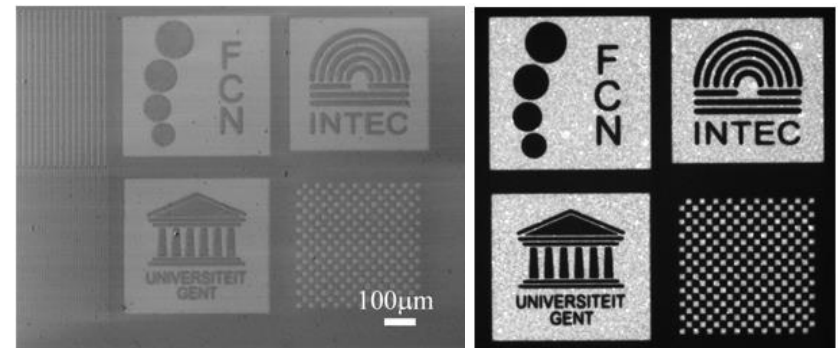
HCl/H₃PO₄ mixture with 1:10 volume ratio



PbS/S²⁻ QD film



CdSe/CdS QD film

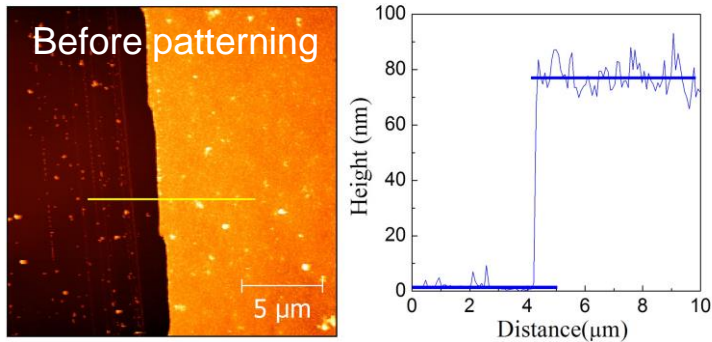


The etching rate for PbS/S²⁻ and PbS/OH⁻ films is ~ 40 nm/min and 45 nm/min, respectively

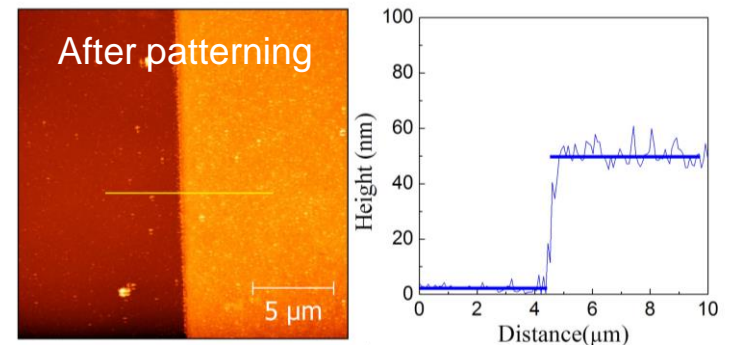
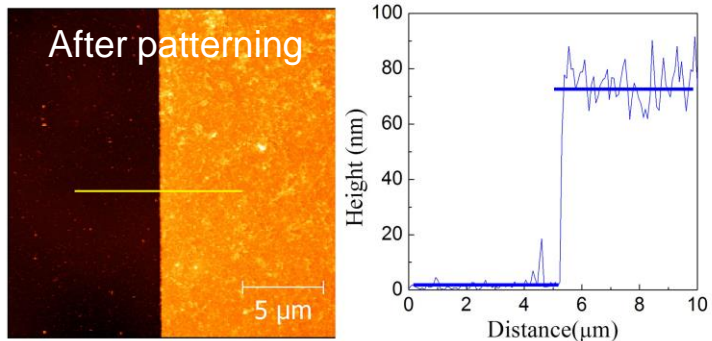
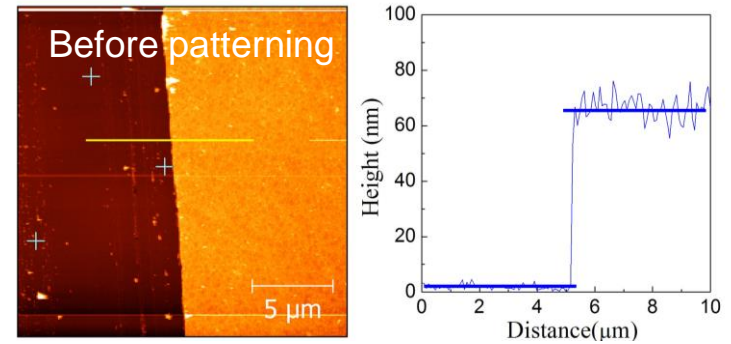
MICROPATTERNING OF PBS NANOCRYSTAL FILM ON 2D SUBSTRATES

Any effect of lithography/patterning on original morphology of the film?

Pbs/S²⁻ QD film



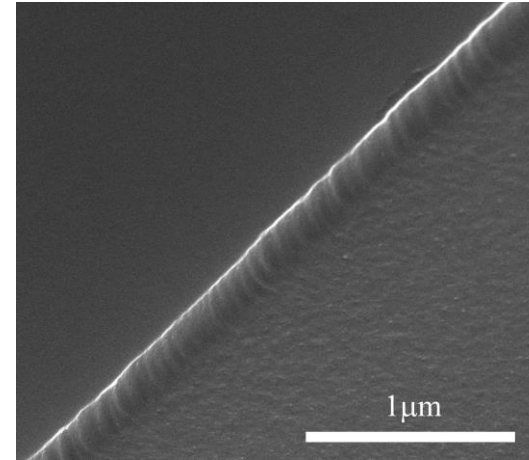
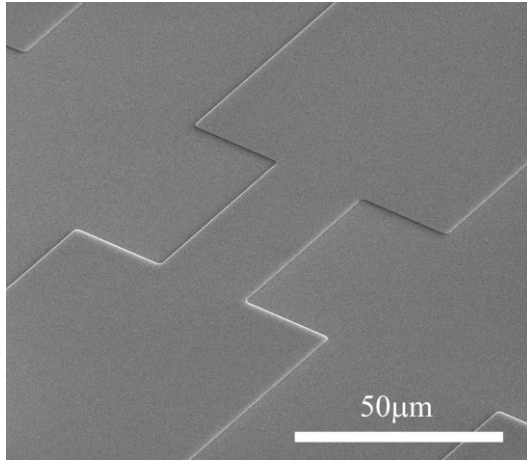
Pbs/OH⁻ QD film



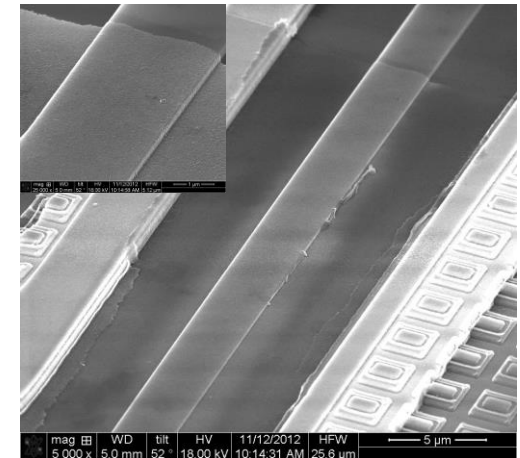
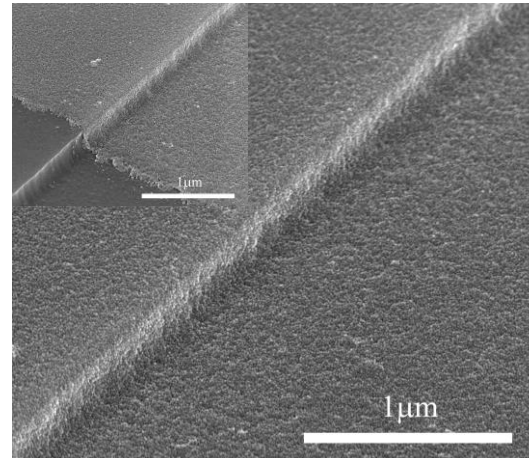
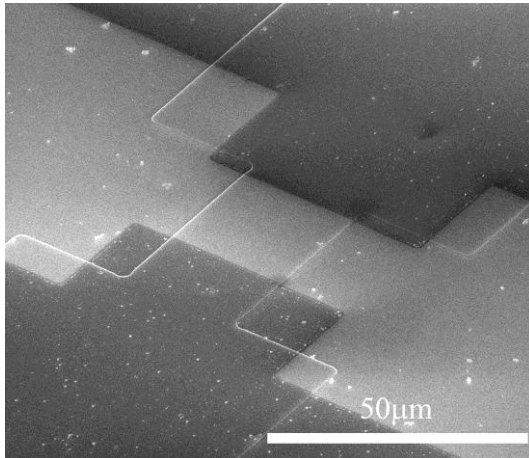
Effect by lithography/patterning is not obvious and can be neglected!

MICROPATTERNING OF PBS NANOCRYSTAL FILM ON 3D SUBSTRATES

SEM measurement of 3D Si substrates:

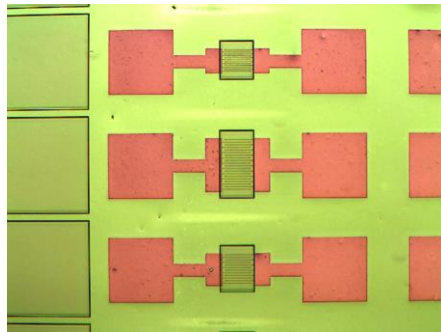


Micropatterned PbS/OH⁻ films on 3D Si substrates and waveguides

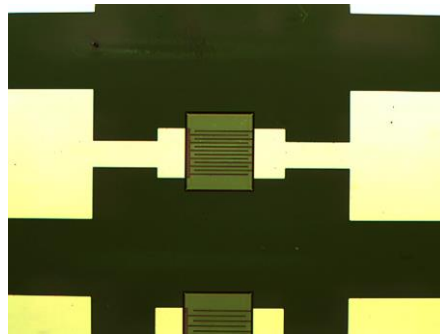


PATTERNING OF PBS NANOCRYSTAL FILM ON PHOTODETECTOR

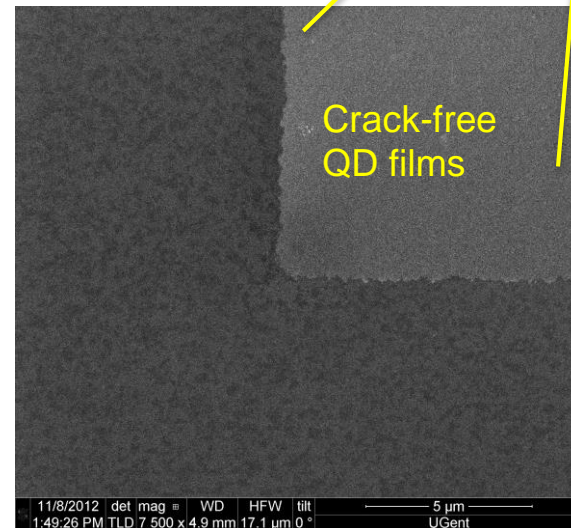
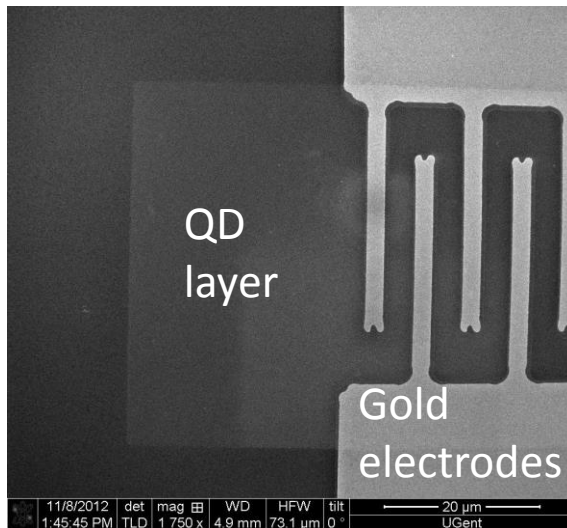
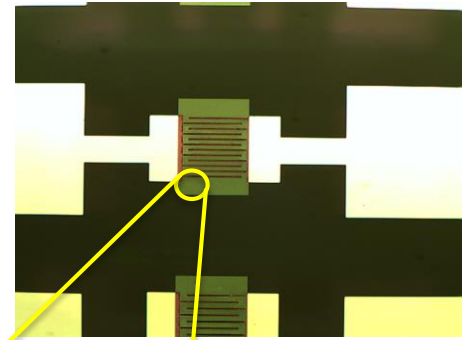
Before etching



Before removing resist



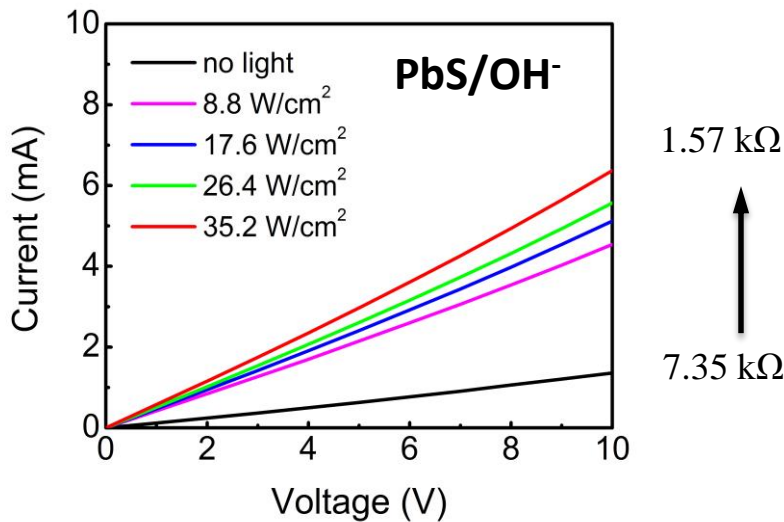
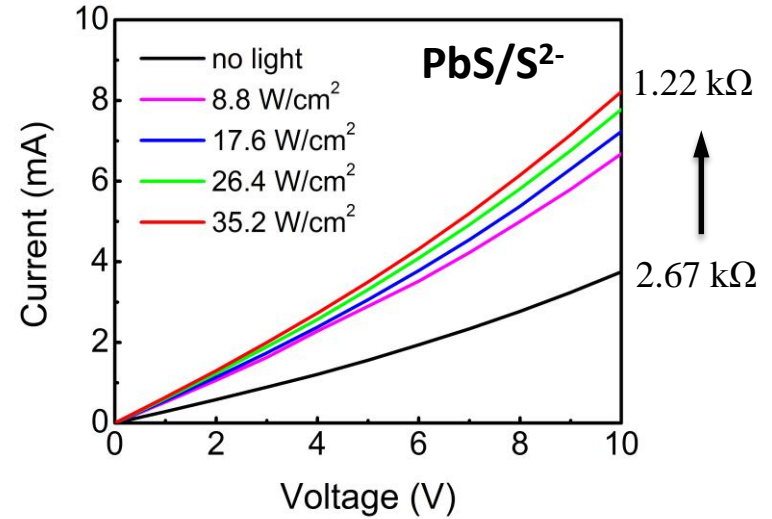
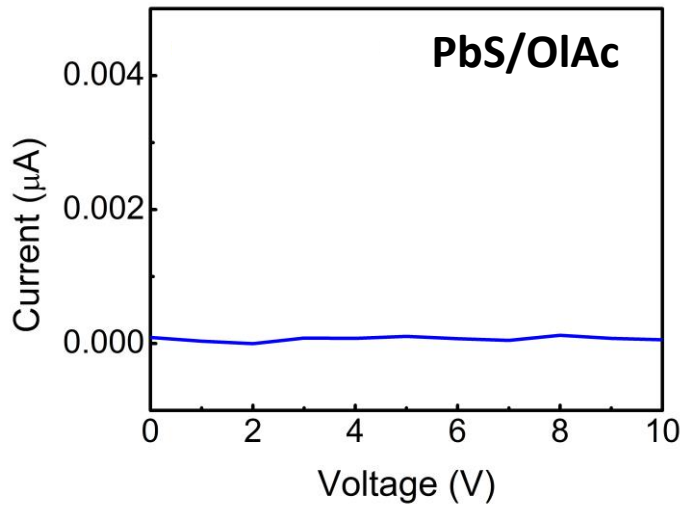
After removing resist



- Introduction
- SWIR/MWIR colloidal quantum dot photodetectors
- Measurement results
- Conclusion and future work

OUTLINE

CHARACTERIZATION OF PbS QD PHOTODETECTOR

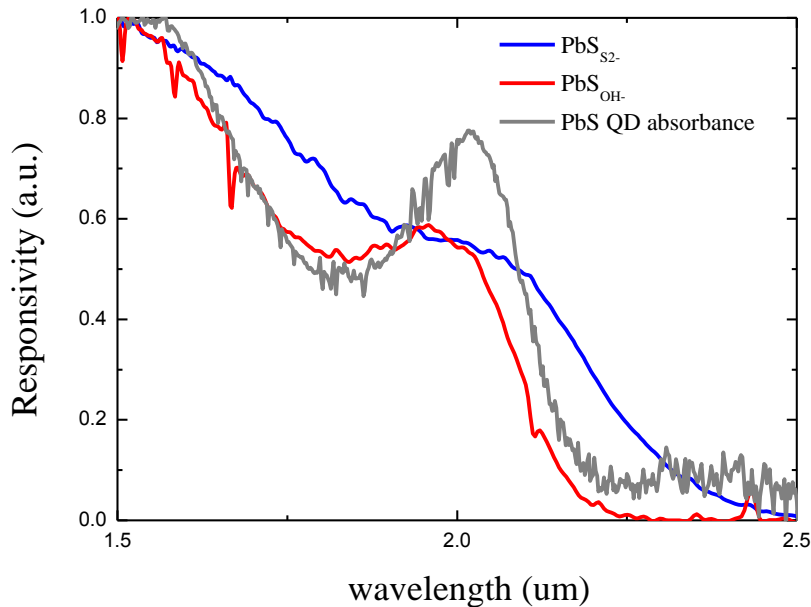


After ligand exchange, the QD films exhibit linear photoconductive property with Au electric contact without Coulomb blockade phenomena

C. Hu, *et al.* PhotWest 2012

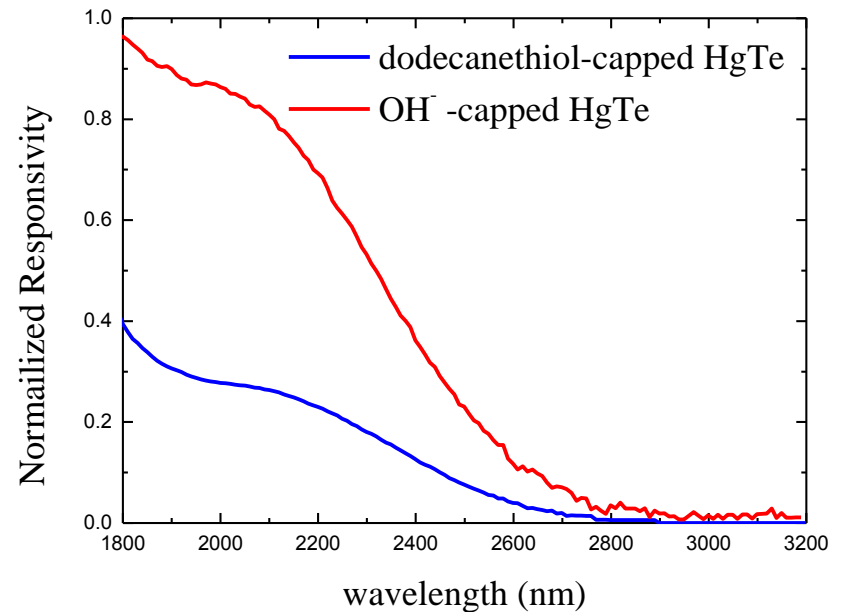
DETECTOR CHARACTERIZATION WITH FTIR

PbS QD photodetector



Spectral response curves nearly match the quantum-confined absorption spectrum

HgTe Photodetector: pushing the cut-off wavelength



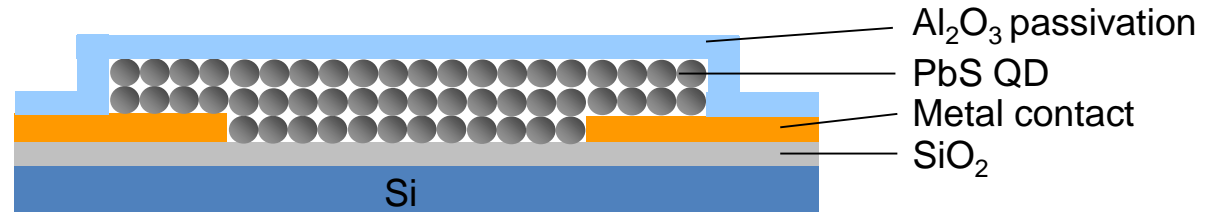
With OH^- ligand exchange, the HgTe QD photodetector has 3 time higher responsivity than dodecanethiol-capped QDs.

Collaboration with Univ Linz

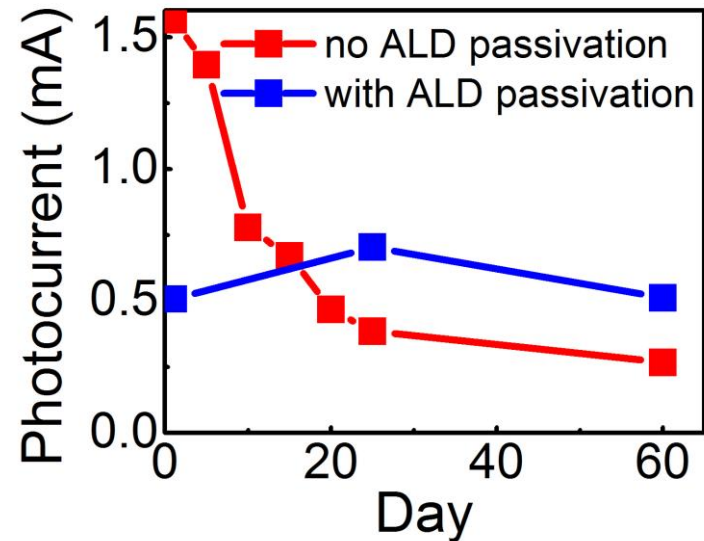
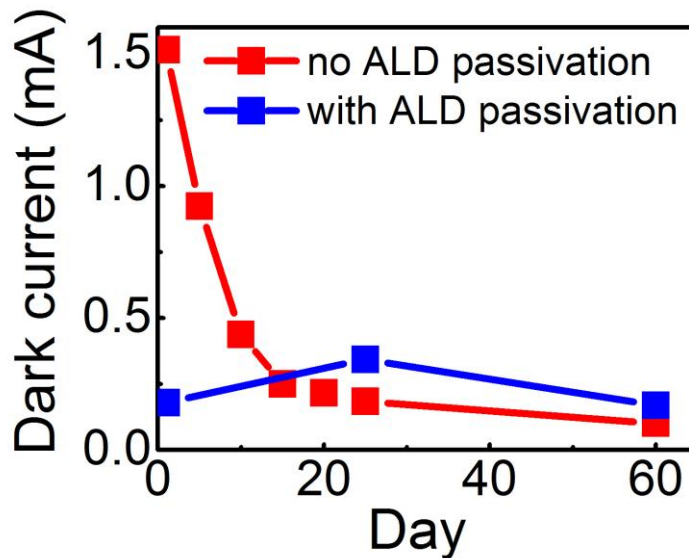
PASSIVATION WITH ATOMIC LAYER DEPOSITION (ALD)

Problem: Degradation of the photodetector due to oxidization

ALD: $\text{Al}_2\text{O}_3 \sim 30 \text{ nm}$

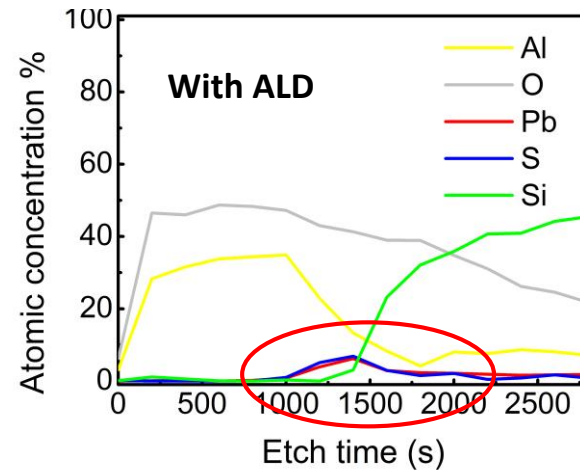
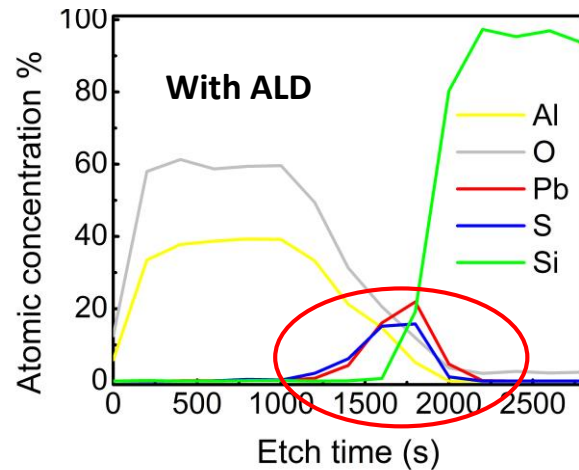
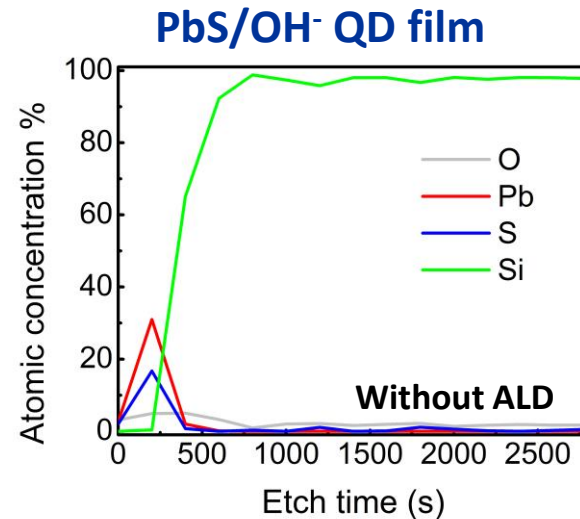
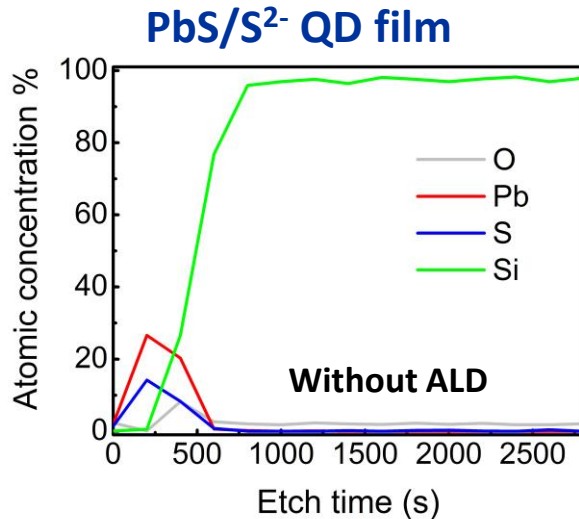


PbS/S²⁻ QD detector (15 LBL)



CHARACTERIZATION ON ALD COATED PBS QD FILM

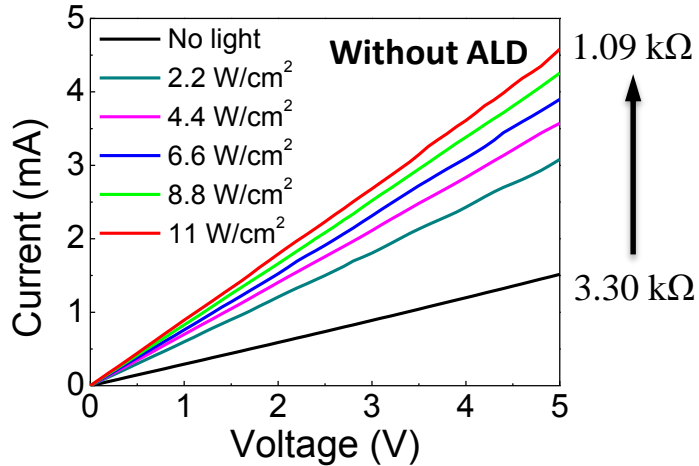
X-ray photoelectron spectroscopy measurement



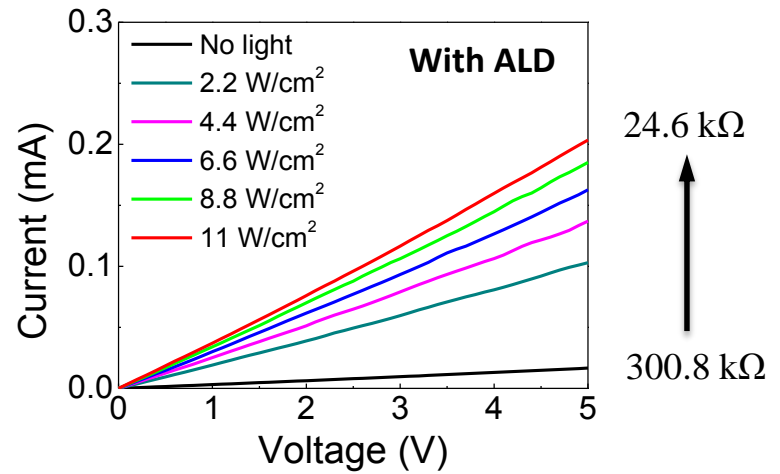
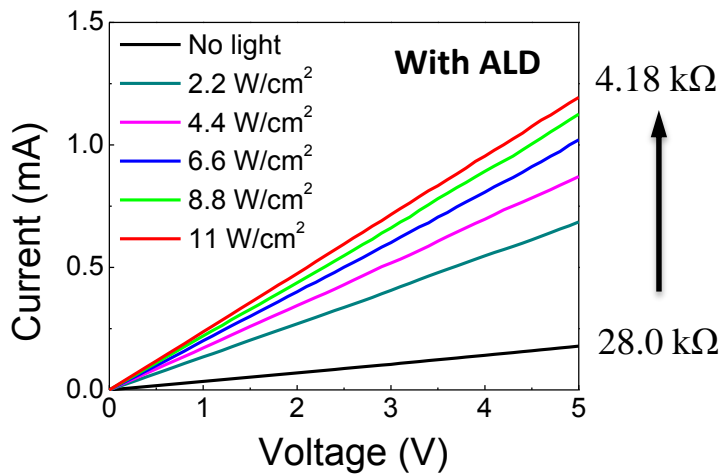
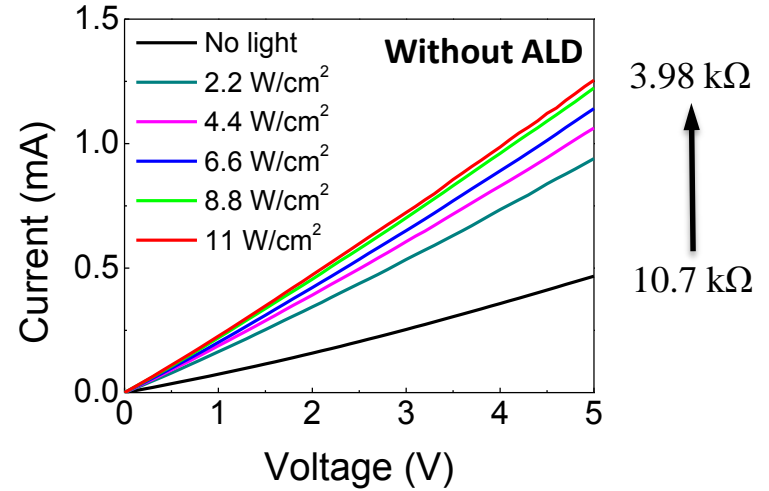
After direct ALD passivation, both dark current/photocurrent are quenched, this can be attributed to alumina penetration during ALD process

CHARACTERIZATION OF PBS QD-ALD PHOTODETECTOR (I)

PbS/S²⁻ QD photodetector

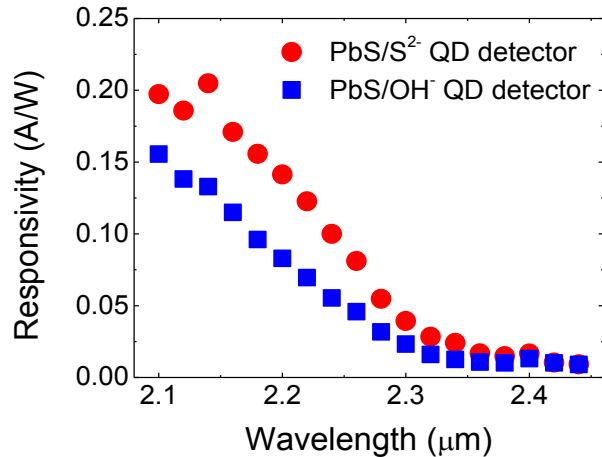


PbS/OH⁻ QD photodetector

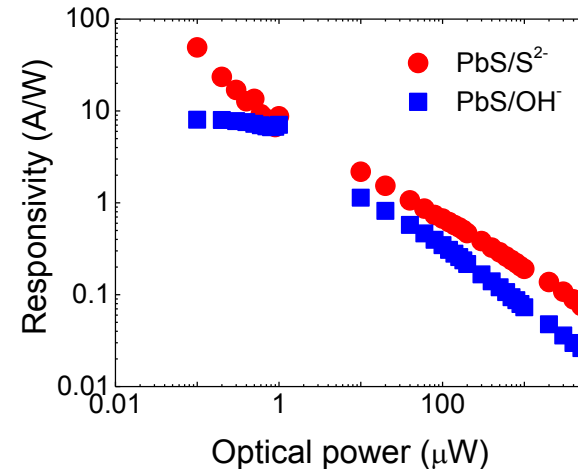


CHARACTERIZATION OF PBS QD-ALD PHOTODETECTOR (II)

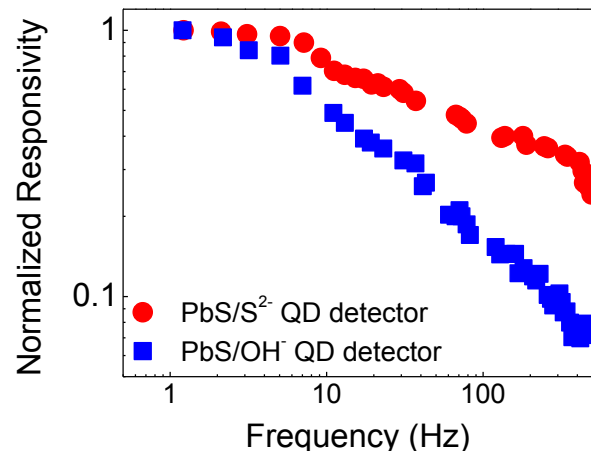
Spectral Response



Responsivity vs. Optical Illumination



Electrical Frequency Response



The corresponding specific detectivity is $\sim 3.4 \times 10^8$ Jones at 300K.

The 3-dB bandwidth of the PbS/S²⁻ and PbS/OH⁻ photodetectors is 40 Hz and 11 Hz, respectively.

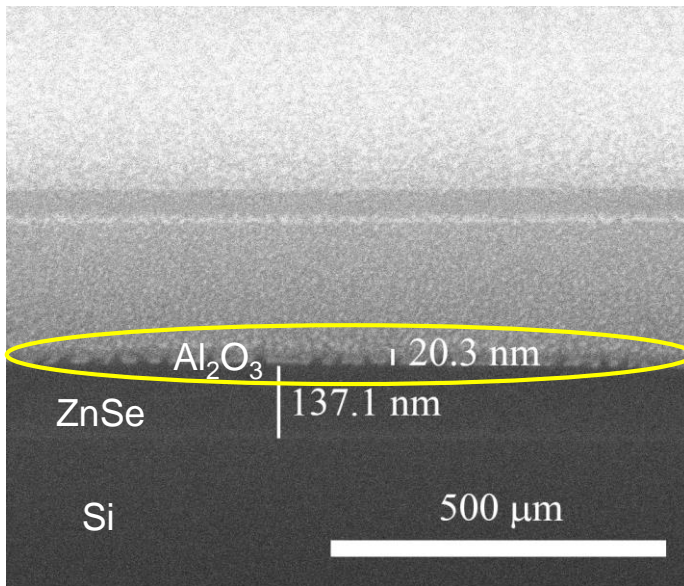
C. Hu, et al. *Applied Physics Letters* 2014

CAN WE IMPROVE PHOTOCURRENT QUENCHING DURING ALD?

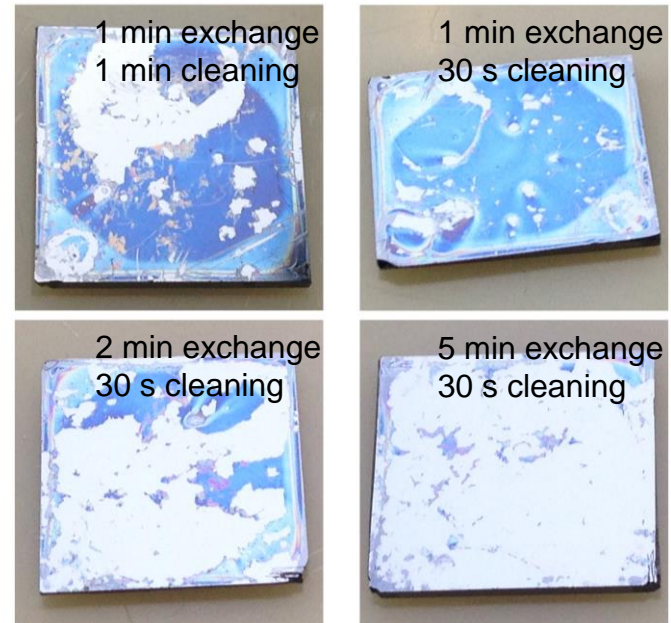
A sacrificial layer with large band gap material before ALD

Route 1: ZnSe QD film as sacrificial layer

Without S²⁻ exchange



With S²⁻ exchange

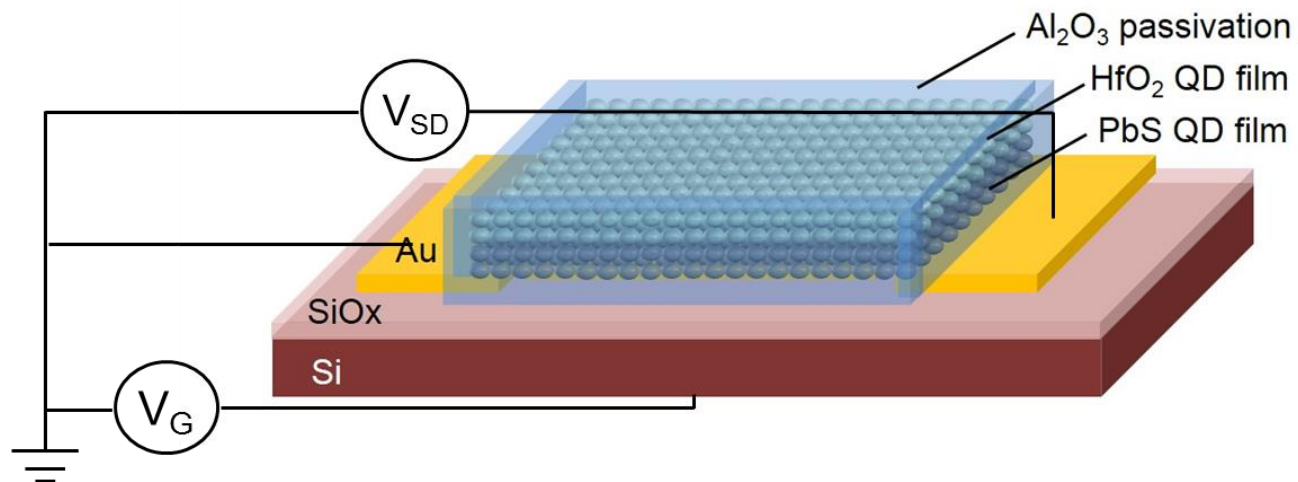
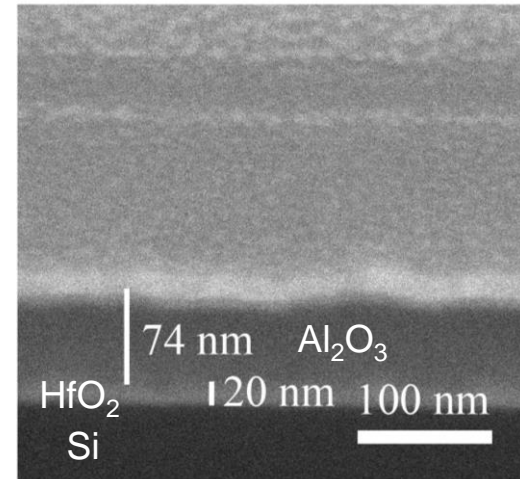
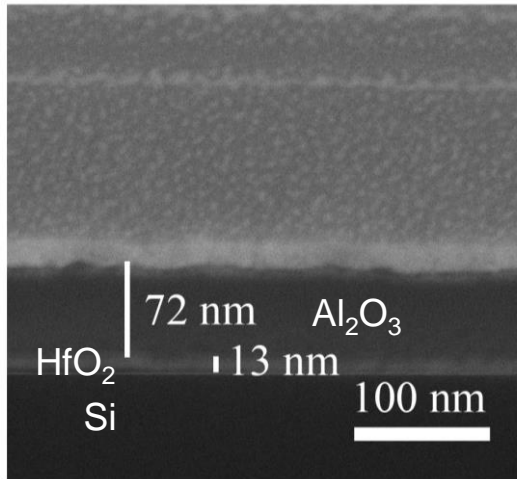


Without ligand exchange, ZnSe film is not compatible with ALD growth

ZnSe QD film peeled off during ligand exchange procedure.

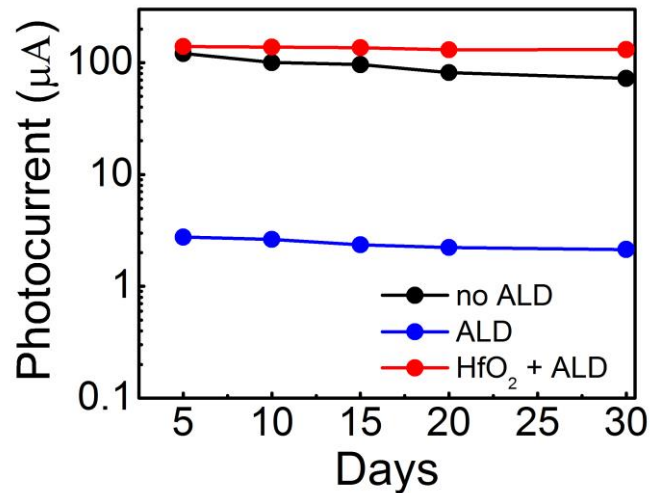
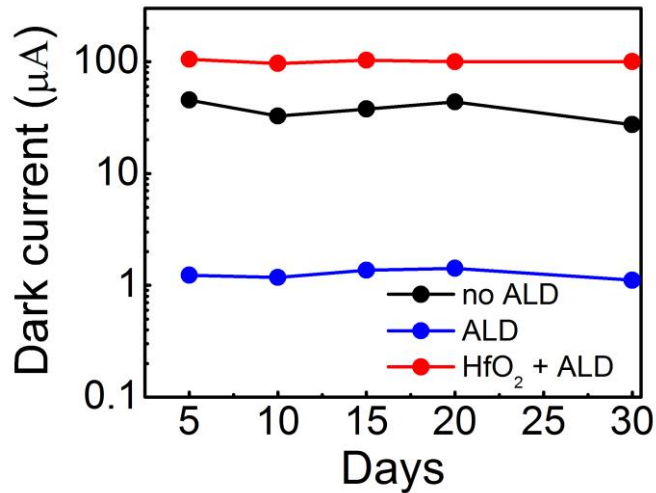
CAN WE IMPROVE PHOTOCURRENT QUENCHING DURING ALD?

Route 2: $\text{HfO}_2\text{-S}^{2-}$ QD film as sacrificial layer exhibits ALD compatibility

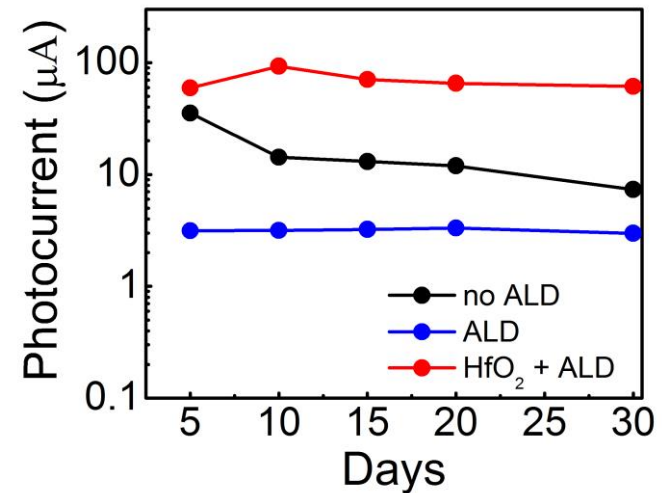
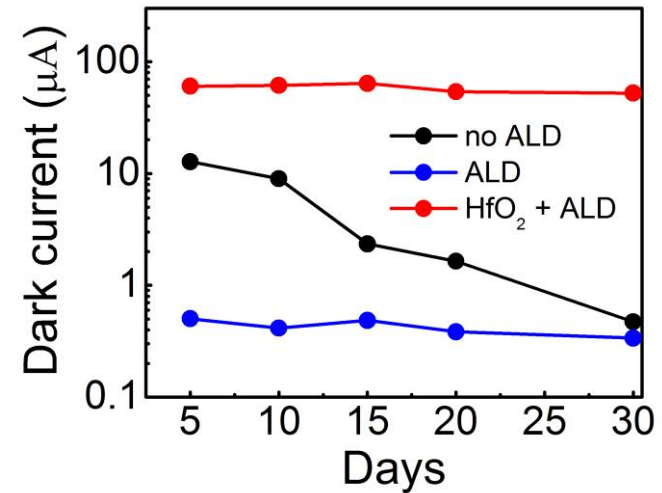


PBS PHOTOTRANSISTOR WITH HfO₂ SACRIFICIAL LAYER

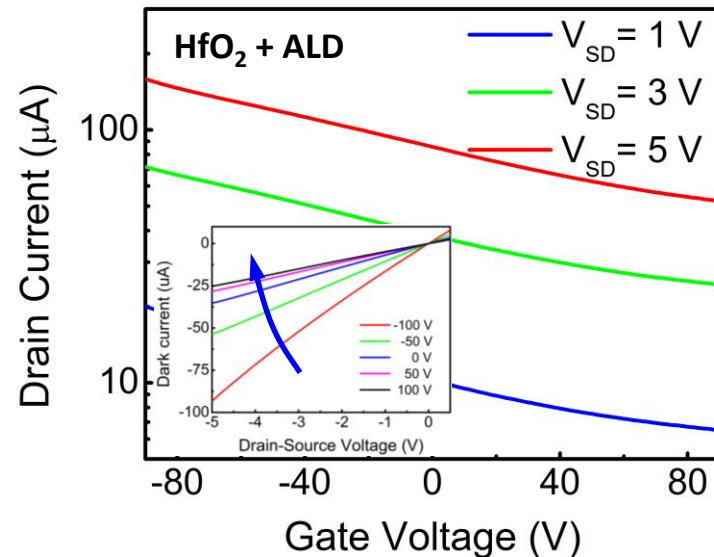
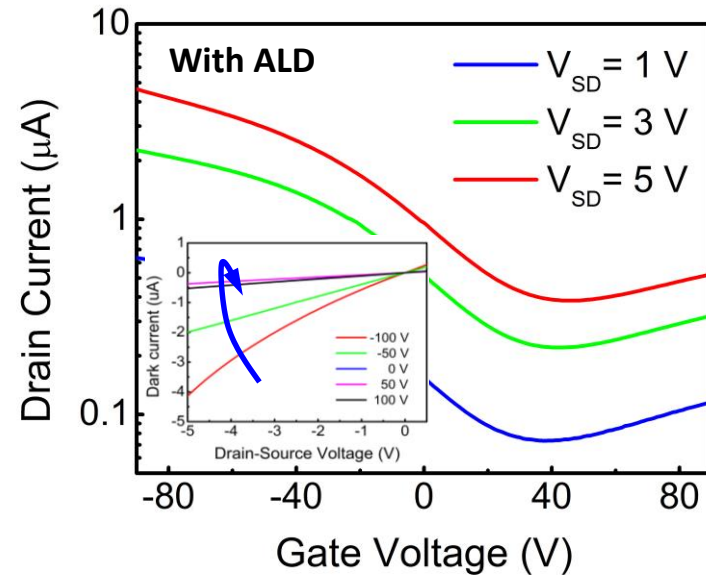
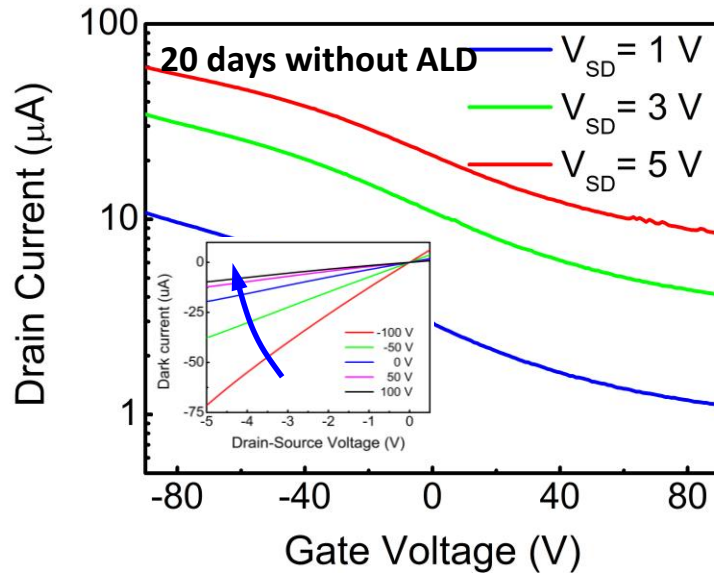
PbS-S²⁻/HfO₂-S²⁻ QD detector (15 LBL)



PbS-OH⁻/HfO₂-S²⁻ QD detector (15 LBL)

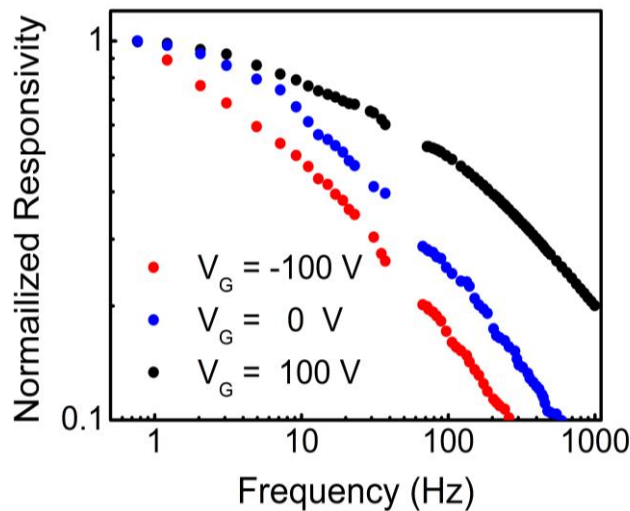
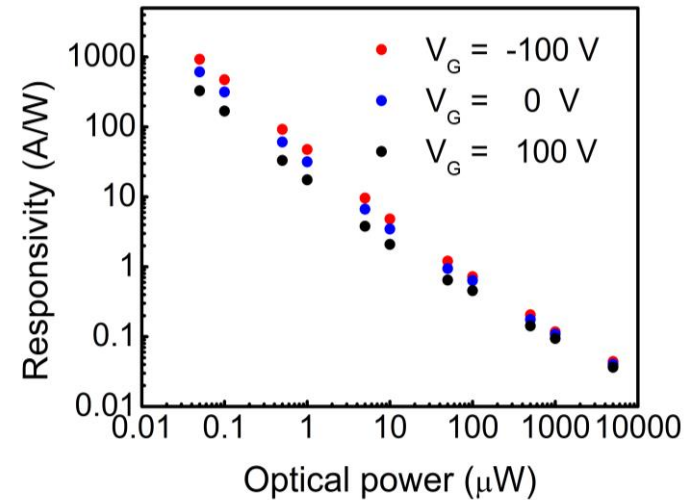
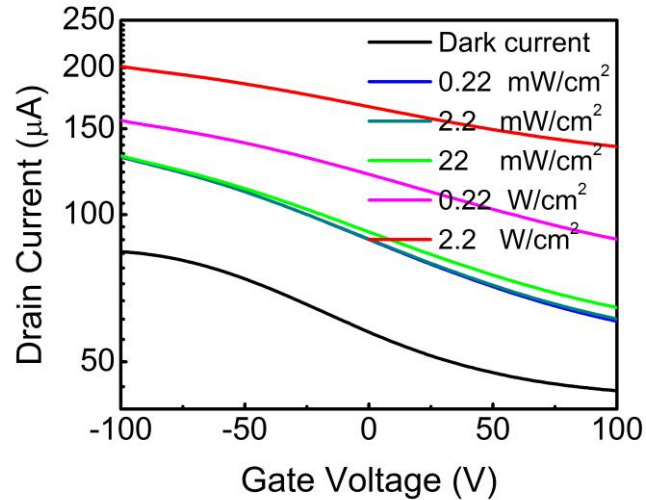


PHOTOTRANSISTOR MEASUREMENT: PbS/S^{2-} QD



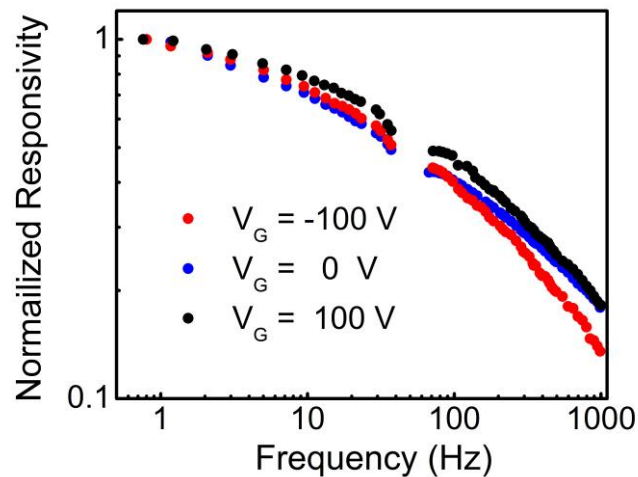
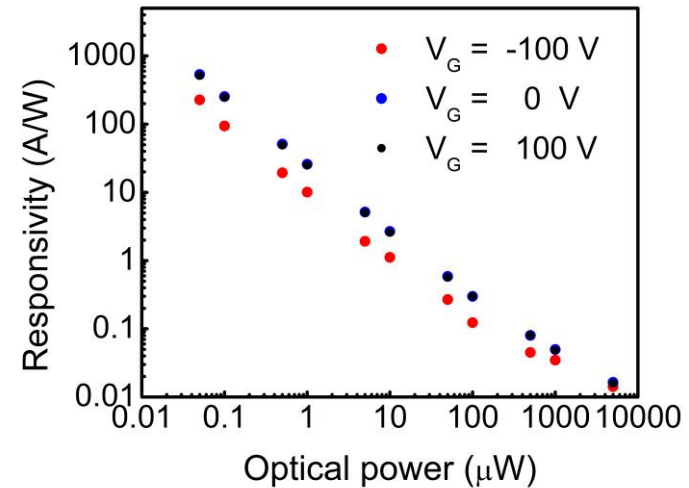
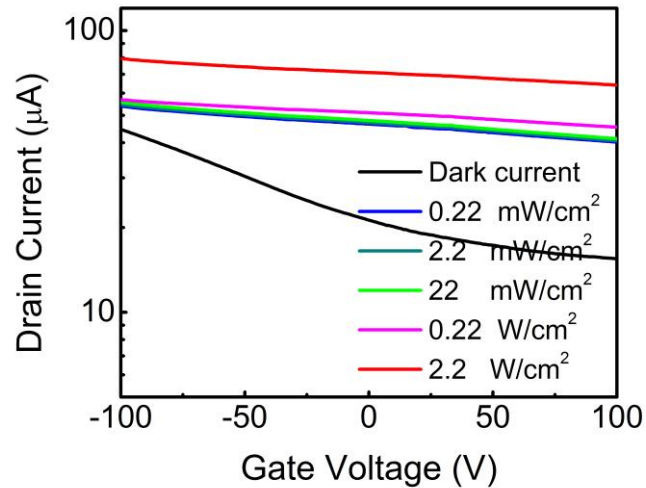
- S^{2-} terminated PbS QD transistors behave as p-type,
- Quasi-linear $I_{SD}-V_D$ curves without saturation of I_{SD} , suggesting large hole densities in the FET channel and can not easily be modulated by gate voltage
- After ALD passivation, PbS- S^{2-} QD transistors behave as ambipolar
- With HfO_2 sacrificial layer, device exhibit p-type again, Calculated holes linear mobility $\mu_{lin} \sim 0.025\text{ cm}^2/(\text{V}\cdot\text{s}) @ 5\text{V}$

CHARACTERIZATION OF PbS/S²⁻- PHOTOTRANSISTOR



- At 5 V Drain bias, $110 \mu\text{W}/\text{cm}^2$ incident power, responsivity ~ 930 A/W @ -100 V gate voltage for PbS/S²⁻ phototransistor;
- The 3-dB bandwidth @ -100 V and @ 100 V gate voltage of the PbS/S²⁻ phototransistors is 3 Hz and 19 Hz, respectively.

CHARACTERIZATION OF PbS/OH^- PHOTOTRANSISTOR



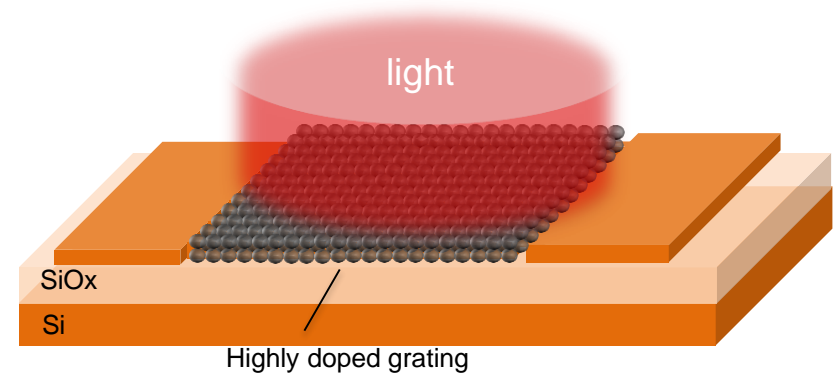
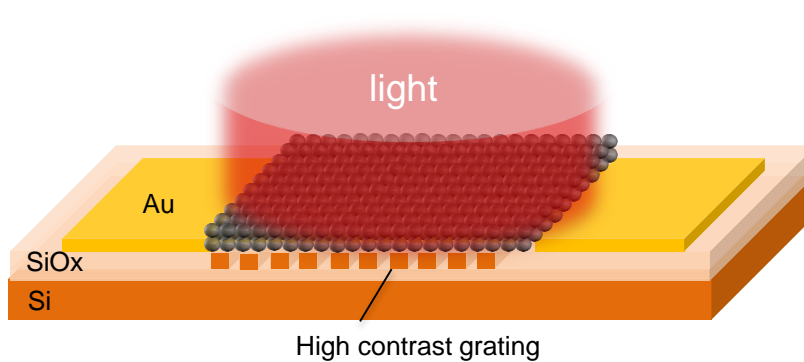
- At 5 V Drain bias, $110 \mu\text{W}/\text{cm}^2$ incident power, responsivity $\sim 230 \text{ A}/\text{W}$ @ -100 V gate voltage for PbS/OH^- phototransistor;
- The 3-dB bandwidth @ -100 V and @ 100 V gate voltage of the PbS/S^{2-} phototransistors is 12 Hz and 17 Hz, respectively.

CONCLUSION

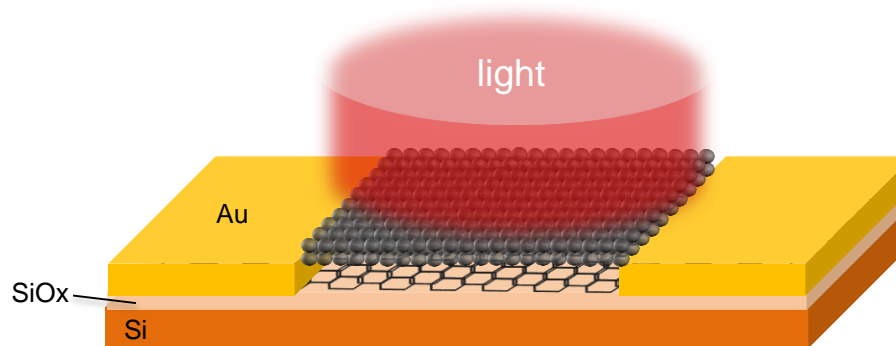
- Crack-free, homogeneous quantum dot films were obtained through a layer-by-layer deposition approach with solid-state ligand exchange
- High resolution colloidal QD films with feature dimensions down to 500 nm can be realized through optical lithography and selective wet etching method for large scale integration applications
- Air-stable PbS colloidal QD photodetectors and phototransistors on Si with high responsivity were obtained

CAN WE FURTHER ENHANCE THE SENSITIVITY?

- Increase the absorption of light in the thin film
⇒ silicon resonant grating structures
- Reduce shadowing from metals
⇒ doped grating



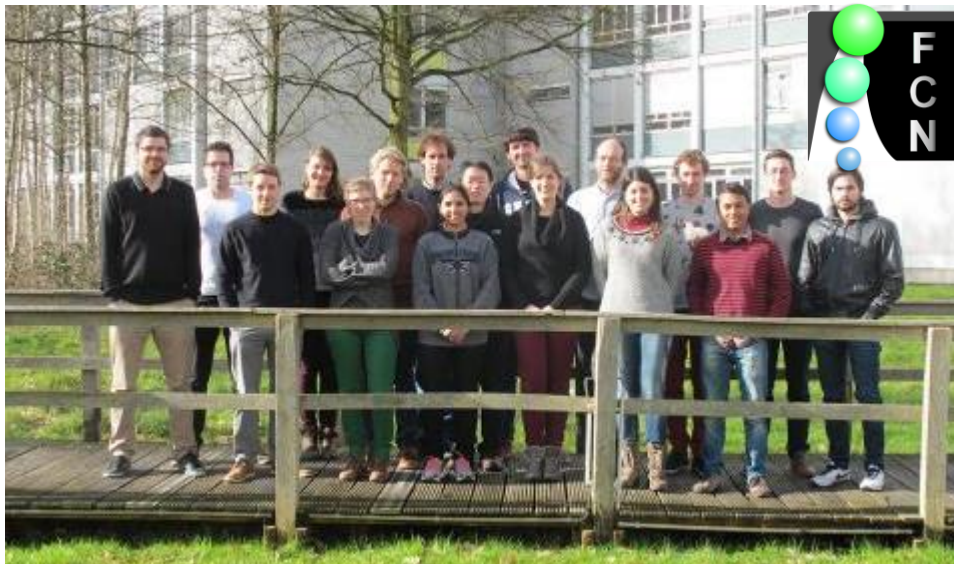
- Enhance the mobility in the film to enhance the internal gain: QD + graphene or “artificial graphene”



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PHOTONICS RESEARCH GROUP

Chen Hu

PhD student

E Chen.Hu@UGent.be



@PhotonicsUGent

T +32 9264 3631

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FOR YOUR ATTENTION!

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